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		FOREI	GN PATENT DOC	UMENTS		•			
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRAN YES/NO		
m	ВА	WO 01/38604 A1	05/31/2001	International			YES Abstract Only		
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m	ВА	Patent Abstracts of Japan, Publication No. 2001-214278 (08/07/2001); http://www19,ipdl.jpo.go.jp/PA1//result/detail/main/wAAA5vaOCTDA413214278P1.htm.							
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M	BA	Database CA Online; Chemical Abstracts Service, Columbus, Ohio; Seita et al.; "Accelerator solution for direct plating and method for direct plating using same"; retrieved from STN Database accession no. 135:11520 CA XP002235694 & JP 2001 214278 A (LeaRonal Japan Inc., Japan); 7 August 2001.										
M	ВВ	Patent Abstracts of Japan; Vol. 017, No. 554 (C-1118), 6 October 1993 & JP 05 156459 A (Hitachi Chem. Co. Ltd.; Others: 01), 22 June 1993.										
m	ВС	MicroPatent Worldwide PatSearch; JP 2002-348673 (04/12/2002); "Electroless Copper Plating Method Without Using Formaldehyde, and Electroless Copper Plating Solution Therefor"; LeaRonal Japan Inc.; Abstract.										
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